

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	1	10/593444	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/18 14:11
S2	3	((MAKIKO) near2 (KITAZOE)).INV.	US-PGPUB; USPAT	ADJ	ON	2009/02/18 14:14
S3	1	((HIROMI) near2 (ITHO)).INV.	US-PGPUB; USPAT	ADJ	ON	2009/02/18 14:14
S4	5	((SHIN) near2 (ASARI)). INV.	US-PGPUB; USPAT	ADJ	ON	2009/02/18 14:14
S5	25	((KAZUYA) near2 (SAITO)).INV.	US-PGPUB; USPAT	ADJ	ON	2009/02/18 14:14
S6	37	hideo.in. and hisayoshi. in.	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/18 14:22
S7	24	S6 and polycrystalline	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/18 14:22
S8	5055	(CVD or deposition) and (tungsten with (coil or wire))	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/18 14:34
S9	1529	S8 and (silicon nitride or SIN)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/18 14:35
S10	1580	"I10" and (hydrogen or "h.sub.2")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/18 14:35
S11	279	S10 and ("427"/\$.ccls. or "428"/\$.ccls.)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/18 14:35
S12	1997	Catalyst (piece or body)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/18 14:37
S13	93	S12 and ("427"/\$.ccls. or "428"/\$.ccls.)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/18 14:38
S14	17	S12 and ("438"/\$.ccls.)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/18 14:39
S15	57	S12 and CVD	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/18 14:41
S16	50	S15 and (hydrogen or "h.sub.2" or treat\$5)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/18 14:44

S17	20	S15 and (hydrogen or "h.sub.2") same \$5treat \$5	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/18 14:45
S18	309305	(siN or silicon nitride or "si.sub.3n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:44
S19	6970	S18 and (ammonia or "nh.sub.3") same plasma and (hydrogen or "h.sub.2") same plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:44
S20	4908	S19 and (ammonia or "nh.sub.3") same plasma same (hydrogen or "h.sub.2") same plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:44
S21	2318	S20 and (water or steam)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:48
S22	811	S21 and pulse	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:49
S23	159	S22 and ((siN or silicon nitride or "si.sub.3n.sub.4").clm. or (siN or silicon nitride or "si.sub.3n.sub.4").ab.)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:49
S24	4504	S18 and (ammonia or "nh.sub.3") with plasma and (hydrogen or "h.sub.2") with plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:50
S25	2900	S24 and (ammonia or "nh.sub.3") with plasma same (hydrogen or "h.sub.2") with plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:51
S26	491	S25 and (pulse) and (water or steam or "h.sub.o")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:51
S27	84	S26 and ((siN or silicon nitride or "si.sub.3n.sub.4").clm. or (siN or silicon nitride or "si.sub.3n.sub.4").ab.)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:51

S28	1059	S25 and (ammonia or "nh.sub.3") with plasma same (hydrogen or "h.sub.2") with plasma same (siN or silicon nitride or "si.sub.3n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:53
S29	196	S28 and (pulse) and (water or steam or "h.sub.o")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:53
S30	36	S29 and ((siN or silicon nitride or "si.sub.3n.sub.4").clm. or (siN or silicon nitride or "si.sub.3n.sub.4").ab.)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:53
S31	48	S27 not S30	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:55
S32	103	(haukka.in. or raaijmakers.in.) and (sin or silicon nitride) and plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:59
S33	5	S32 and (hydrogen or "h.sub.2") plasma same (nitrogen or ammonia or "nh.sub.3" or "n.sub.2") plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 15:59
S34	160	S29 not (S30 or S31)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 16:05
S35	58742	S18 and ((siN or silicon nitride or "si.sub.3n.sub.4").ti. or (siN or silicon nitride or "si.sub.3n.sub.4").ab.)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 16:06
S36	3310	S35 and (pulse or cycle)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 16:07
S37	8	S36 and (ammonia or "nh.sub.3") adj2 plasma same (hydrogen or "h.sub.2") adj2 plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 16:07
S38	5	("6911391").URPN.	USPAT	ADJ	ON	2009/02/19 16:09
S39	20	S36 and (ammonia or "nh.sub.3") adj2 plasma and (hydrogen or "h.sub.2") adj2 plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 16:10

S41	526	silicon nitride same plasma.ab.	USPAT	ADJ	ON	2009/02/19 16:27
S42	23	S41 and (ammonia or "nh.sub.3") adj2 plasma and (hydrogen or "h.sub.2") adj2 plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 16:29
S43	6230	(silane or "sih.sub.4") same (ammonia or "nh.sub.3") same (hydrogen or "h.sub.2")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 16:33
S44	2101	S43 and (silane or "sih.sub.4") same (ammonia or "nh.sub.3") same (hydrogen or "h.sub.2") same plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 16:33
S45	1703	S44 and (siN or silicon nitride or "si.sub.3n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 16:34
S46	554	S45 and (siN or silicon nitride or "si.sub.3n.sub.4").clm.	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 16:35
S48	303	S45 and catalyst	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 16:38
S57	17	("6124171").URPN.	USPAT	ADJ	ON	2009/02/19 17:11
S58	1636	(siN or silicon nitride or "si.sub.3n.sub.4") same (hydrogen or "h.sub.2") (gas or plasma)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 17:16
S59	610	(siN or silicon nitride or "si.sub.3n.sub.4") same (hydrogen or "h.sub.2") (gas or plasma) same (ammonia or "nh.sub.3")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 17:16
S61	1999	Catalyst (piece or body)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 17:44
S62	114	S61 and (siN or silicon nitride or "si.sub.3n.sub.4")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 17:44
S63	55	S61 and (siN or silicon nitride or "si.sub.3n.sub.4") and (hydrogen or "h.sub.2")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 17:45

S64	127	S18 and (SiN or silicon nitride or "Si.sub.3N.sub.4") same (ammonia or "NH.sub.3") (plasma or treatment) and (hydrogen or "H.sub.2") (plasma or treatment)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/19 18:04
S66	10373	(silicon nitride or SiN or "Si.sub.3N.sub.4") and (ammonia or "NH.sub.3") and (DCS or "SiH.sub.2Cl.sub.2")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/23 13:11
S67	1781	(silicon nitride or SiN or "Si.sub.3N.sub.4") and (ammonia or "NH.sub.3") same (DCS or "SiH.sub.2Cl.sub.2")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/23 13:11
S68	519	(silicon nitride or SiN or "Si.sub.3N.sub.4") and (ammonia or "NH.sub.3") same (DCS or "SiH.sub.2Cl.sub.2") same plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/23 13:11
S69	519	(silicon nitride or SiN or "Si.sub.3N.sub.4") and (ammonia or "NH.sub.3") same (DCS or "SiH.sub.2Cl.sub.2") same plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/23 15:02
S70	293	S69 and (silicon nitride or SiN or "Si.sub.3N.sub.4") same (ammonia or "NH.sub.3") same (DCS or "SiH.sub.2Cl.sub.2") same plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/23 15:02
S71	36	S69 and (silicon nitride or SiN or "Si.sub.3N.sub.4") same (ammonia or "NH.sub.3") same (hydrogen or "H.sub.2") same (DCS or "SiH.sub.2Cl.sub.2") same plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/23 15:03
S75	1	S69 and (silicon nitride or SiN or "Si.sub.3N.sub.4") same (hydrogen or "H.sub.2") (plasma or post treat\$4)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/23 15:21

S76	490	(silicon nitride or SiN or "Si.sub.3N.sub.4") same (hydrogen or "h.sub.2") (plasma or post treat\$4)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/23 15:22
S77	2	"20020052124"	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 08:08
S78	2003	Catalyst (piece or body)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 08:10
S79	956	S78 and (hydrogen or "h.sub.2")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 08:10
S80	855	S78 and (hydrogen or "h.sub.2") same catalyst	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 08:12
S81	29	S80 and (hydrogen or "h.sub.2") same catalyst (perform\$4 or clean\$3)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 08:13
S84	25	S80 and (hydrogen or "h.sub.2") same catalyst (perform\$8)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 08:15
S86	956	S78 and (hydrogen or "h.sub.2")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 08:17
S87	3	S86 and (tokyo.as. or matsuzaki.in. or kitamura.in. or kitazoe.in. or saito.in.)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 08:17
S89	23	S78 and (tokyo.as. or matsuzaki.in. or kitamura.in. or kitazoe.in. or saito.in.)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 08:25
S90	5	S89 and film	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 08:26
S91	32	S78 and (tokyo.as. or matsuzaki.in. or kitamura.in. or kitazoe.in. or saito.in. or matsumura.in. or izumi.in. or masuda.in. or nashimoto.in. or miyoshi.in. or nomura.in. or sakurai.in. or aoshima.in.)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 08:27
S92	11	S91 and film	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 08:27

S93	325	nitride same (ammonia or "nh.sub.3") (plasma or treatment or anneal \$4) same (hydrogen or "h.sub.2") same plasma	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 08:41
S96	343	(siN or silicon nitride or "si.sub.3n.sub.4") same (ALD or atomic layer deposition) same (ammonia or "NH.sub.3")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 09:24
S97	2	"20020040847"	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 09:32
S98	9077	silicon nitride with (multi-layer\$2 or cyclic or lamina\$5)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 09:44
S100	18	silicon nitride with (multi-layer\$2 or cyclic or lamina\$5) with uniform\$2	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 09:45
S101	6	S98 and multi-layered silicon nitride	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 09:47
S102	5979	silicon nitride with (multi-layer\$2 or cyclic or laminant or laminated)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 09:48
S103	10	S102 and silicon nitride with (multi-layer\$2 or cyclic or laminant or laminated) same uniformity	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 09:48
S104	364	silicon nitride same polycrystalline silicon same (laminant or laminated)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:00
S106	288	(DCS or dichlorosilane) same (chlorine or halogen) same (ammonia or "NH.sub.3")	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:09
S107	45	S106 and (DCS or dichlorosilane) same (chlorine or halogen) same (ammonia or "NH.sub.3") same (layer or multi-layer or ALD or atomic layer)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:10

S108	1	S106 and (DCS or dichlorosilane) same (chlorine or halogen) and (sin or silicon nitride) same (ammonia or "NH. sub.3") (plasma or treatment)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:16
S109	4	(chlorine or halogen) same (sin or silicon nitride) same (ammonia or "NH. sub.3") (plasma or treatment)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:17
S110	19	(chlorine or halogen) with remov\$3 same (ammonia or "NH. sub.3") (plasma or treatment)	US-PGPUB; USPAT; EPO; DERWENT	ADJ	ON	2009/02/25 10:19

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